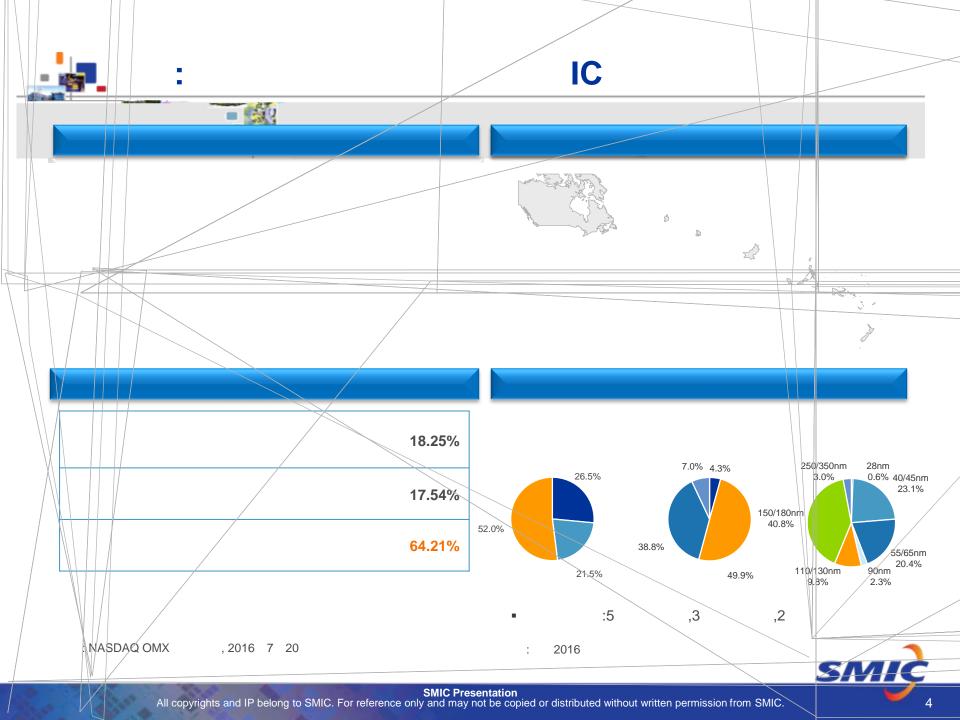


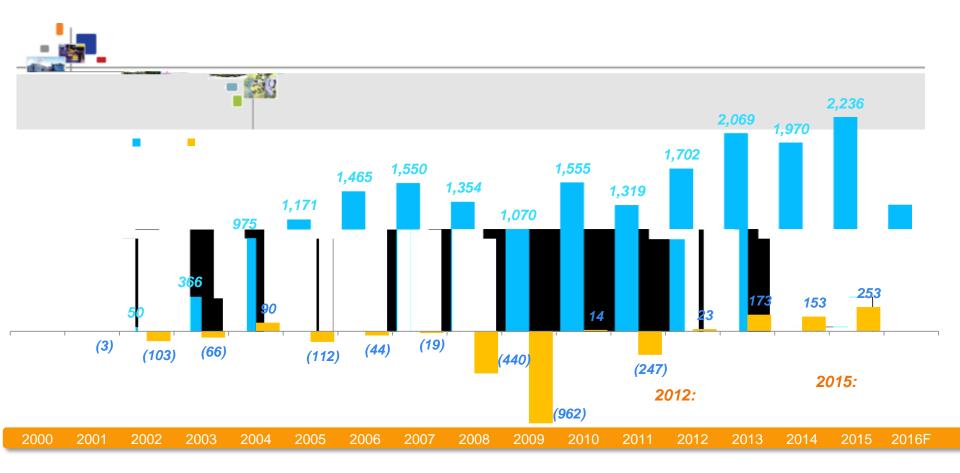
SMI

0981-HK

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1995
1995
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20-F 6-K









2009-2015

William Tudor Brown

Cadence Design

Systems, Inc.

(NEA)

2013 ,









- **2009 2015:**
- **2008 2009:**
- **2002** 2008:





- NEC **2009 2011:**
- 2007 2009: Silterra Malaysia
- **2005** 2006:
- **2001 2005**:
- **1996 2001:**
- 1984 1996: AT&T



































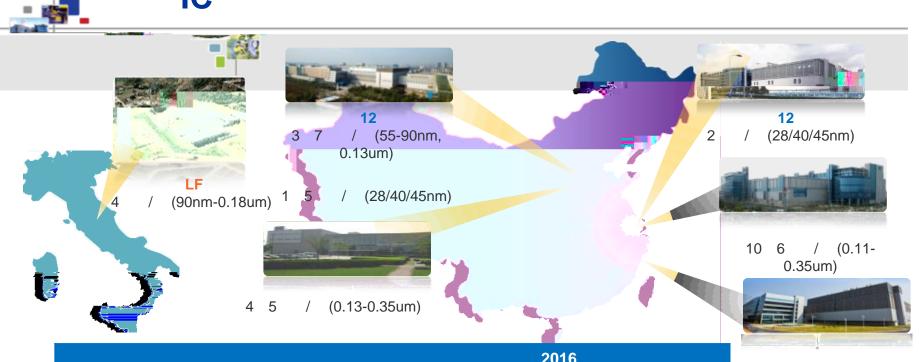


-88⁻⁷/₋₄₃ -166

2016 2







	2	2016	
45nm	20K	20K	~20K
55-90nm, 0.13um	37K	45K	~50K
45nm	15K	18K	~35K
0.11-0.35um	106K	-	~106K
0.13-0.35um	45K	-	~45K
0.15-0.35um	26K	31K	~50K
90nm-0.18um	40K	-	~50K



(0.15-0.35um)

2

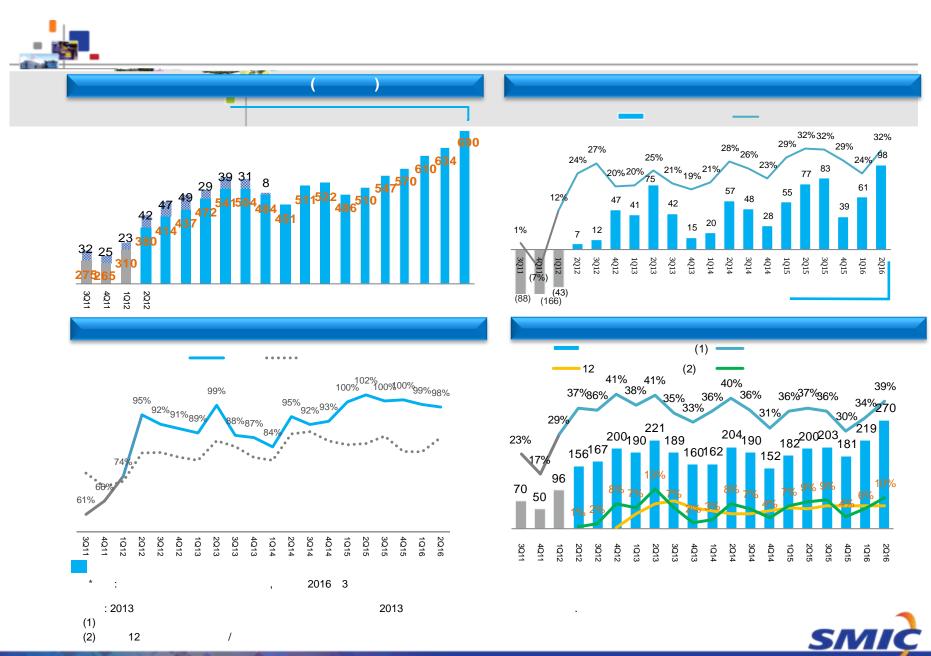
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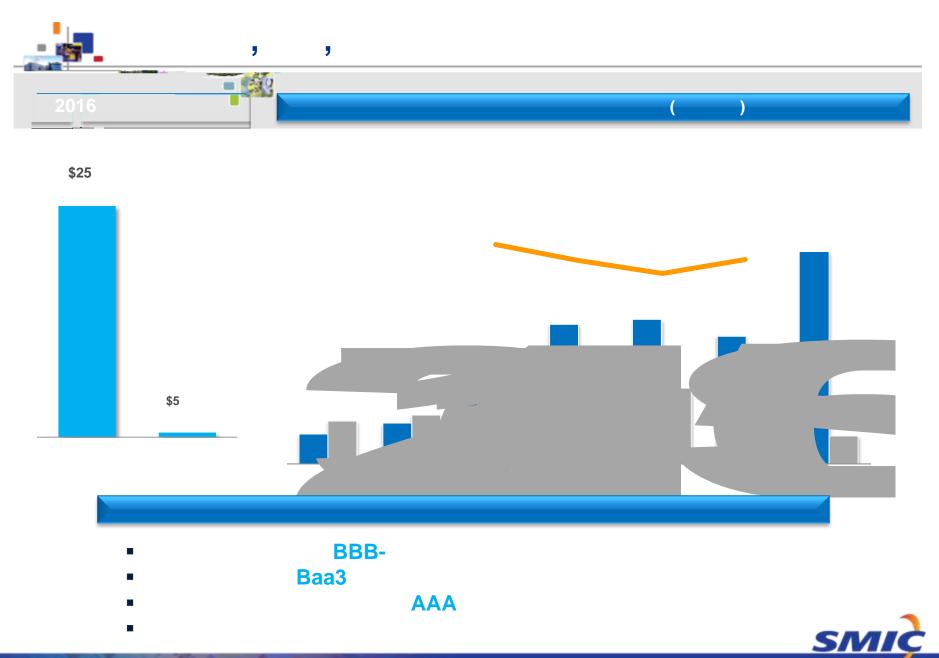




- 口简介
- □中芯业绩
- 口中国半导体行业机遇
- □获利成长战略
- □总结











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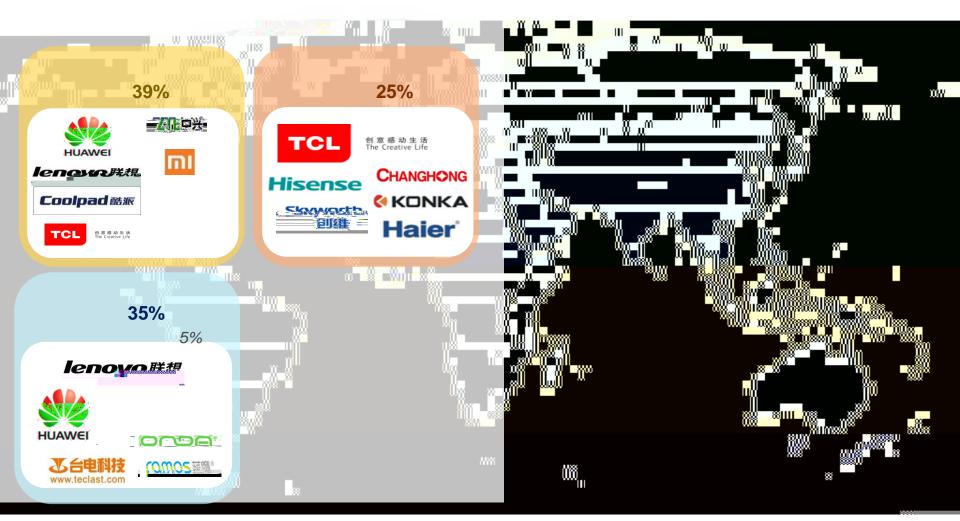
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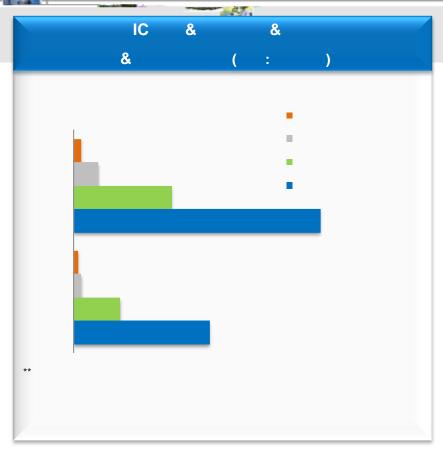
147





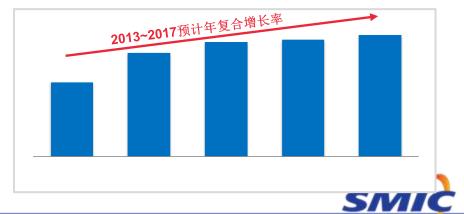
















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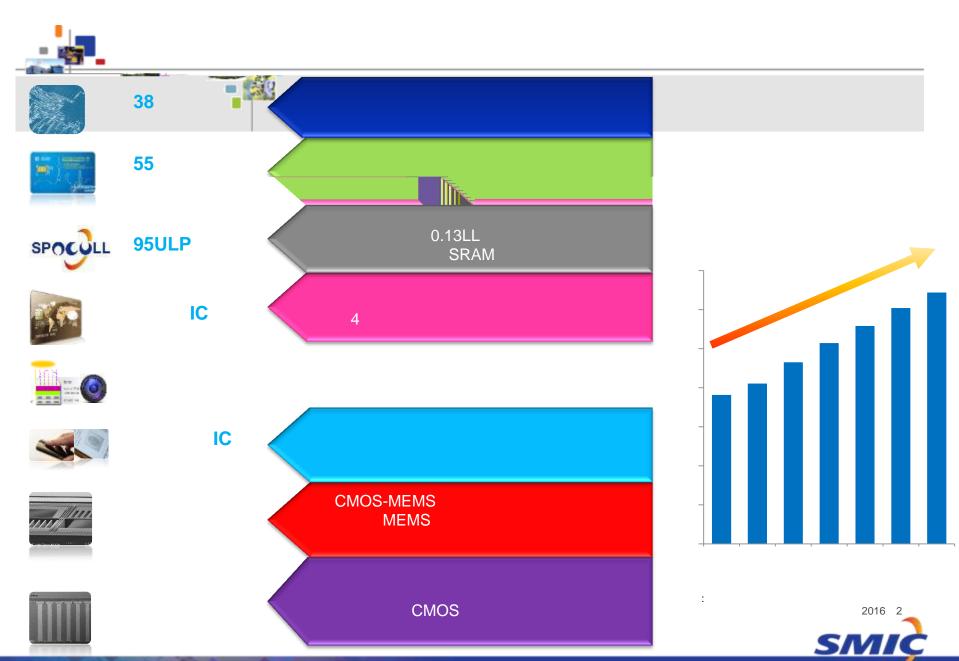








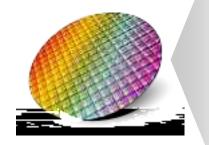












- 8

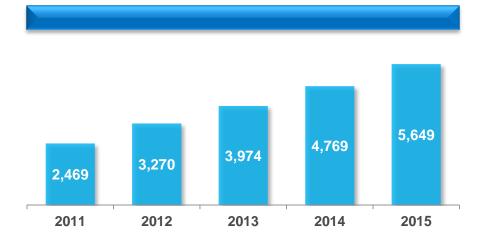
0.13LL 0.13LL SRAM

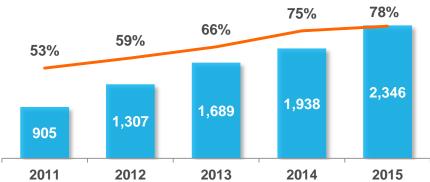
■ SPOCULL --- <u>SMIC POly Contact for Ultra Low Leakage</u>























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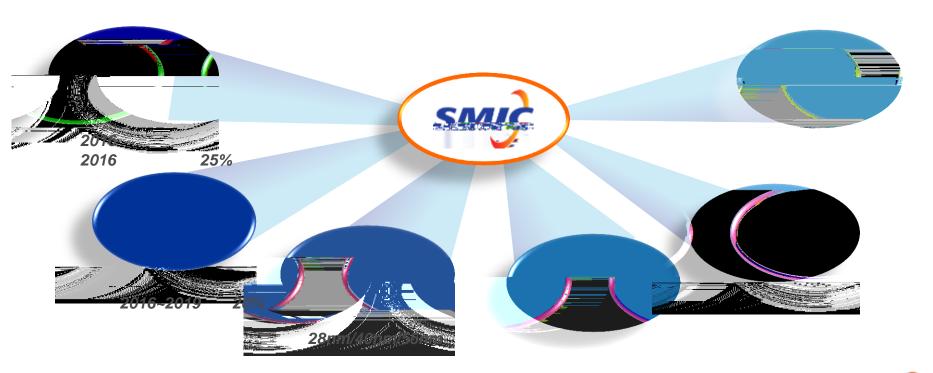






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: ir@smics.com

